Thrust B

Ozonated Water Research Directions

Sangwoo Lim

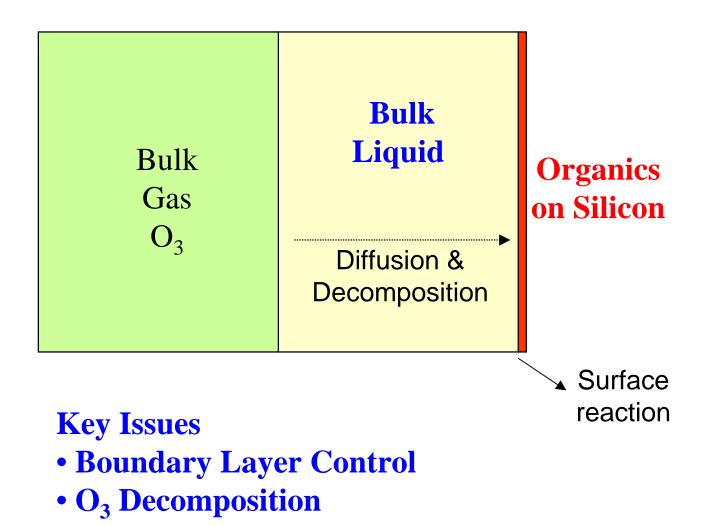
Dept. of Electrical Engineering Stanford University

Ozonated Water Cleaning Impact

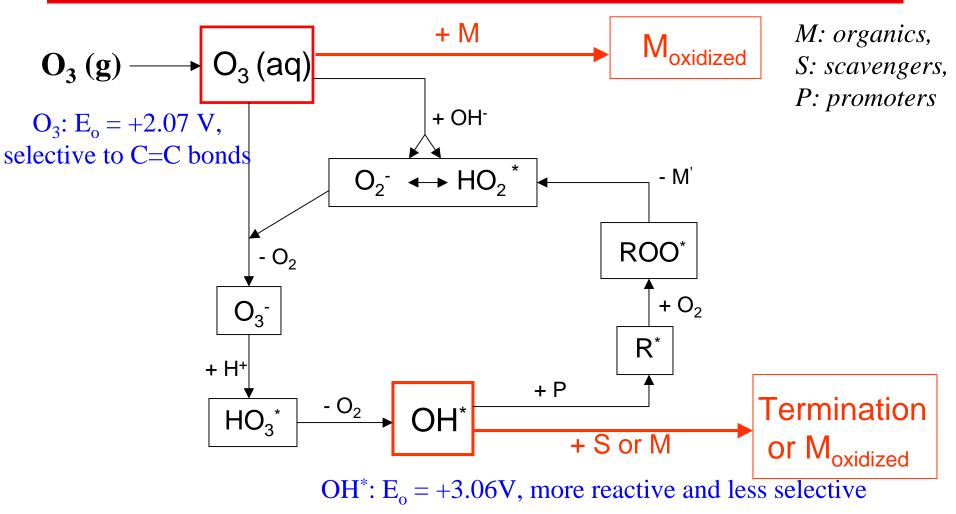
Resist striping & replacement for Piranha cleaning

- CoO; 29% reduction compared to piranha.
- Environmental Gain
 - Eliminates most H_2SO_4 use and waste.
 - Less UPW use, due to elimination of H_2SO_4 rinse.
- Safety
 - Eliminates exposure to hot piranha
 - Need to learn how to handle O_3 safely.

Process



O₃ Decomposition Model



Staehelin, et al., Environ. Sci. Technol. 1985, 19, 1206

Chain Reaction Chemistry

- 1. Direct consumption of O_3 , e.g., phenol
- 2. Initiation of O_3 decomposition, e.g., OH^2 , glyoxylic acid
- 3. Propagation, e.g., formic acid, methanol

(OH^{*} scavenged, but O_2^{*-} reformed.)

4. Termination, e.g., tert-butanol, HCO_3^{-1} , CO_3^{2-1} (OH^{*} scavenged, and no O_2^{*-} or H_2O_2 formed.)

Cleaning Parameters

S. De Gendt et al., Symp. on VLSI Technol. p.168, 1998.

- pH ↑ : [O₃] ↓
- promoter addition $[H_2O_2]$ \uparrow : $[OH^*]$ \uparrow , $[O_3]$ \downarrow ,

resist removal 🗼

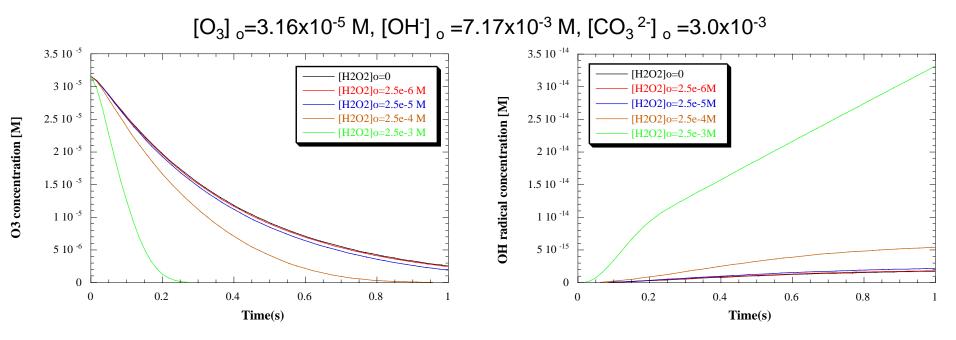
- inhibitor addition [CH₃COOH][↑]: [OH^{*}] ↓, [O₃] , resist removal .
- Temperature ↑: [O₃] ↓, but removal efficiency/[O₃] ↑

What is the chemical structure of various resists? What are the water-soluble etch products?

Numerical Simulation

- Simulates direct and indirect oxidant concentrations.
- Predict the distribution of intermediate species.
- Examines the kinetic roles of scavengers and promoters on O₃ and OH^{*} concentrations

Simulation Results





- Which oxidation is preffered, direct or indirect?
 - What is the oxidation mechanism of resist?
 - What is the main etch species, O_3 or OH^* ?
- Is the decomposition model realistic?

Future Work

- Gathering all kinetic data and Remodeling.
- Combining of simulation and experimental data.
- Elucidating O₃ decomposition and cleaning efficiency.
 - pH,
 - scavengers,
 - promoters.....